

In the claims:

Please substitute the following full listing of claims for the claims as originally filed or most recently amended.

1. (Currently amended) A lithography system, comprising:

a reticle chamber containing a reticle stage component extending between portions of an optics system,

said reticle chamber having a reticle chamber opening that provides direct access to a-said reticle stage within the-said reticle chamber so that the-said reticle stage can be accessed or removed through the said reticle chamber opening and from between said portions of said optics system without disassembly of components of said optics system.

Claim 2 has been cancelled.

3. (Currently amended) The lithography system of claim 1, wherein the-said reticle stage component includes a reticle stage and a reticle table, wherein said reticle stage component is removable from the-said reticle chamber in a first direction which is in a plane substantially horizontal to a-said reticle table mounted to the-said reticle stage.

4. (Currently amended) The lithography system of claim 1-21, wherein a-said reticle chamber maintenance panel is pivotably mounted to the-said reticle chamber.

5. (Currently amended) The lithography system of claim 1, wherein the-said reticle chamber opening is at an angle substantially equal to or between 0° and 45° with relation to the-said reticle chamber.

6. (Currently amended) The lithography system of claim 1, wherein ~~the~~said reticle chamber opening is at an angle at or greater than 45° with relation to ~~the~~said reticle chamber.

7. (Currently amended) The lithography system of claim 1, ~~further comprising~~ wherein said optics system comprises:

a projection optic system; and  
an illuminator optic system; and  
wherein said ~~a~~ reticle table mounted to ~~the~~said reticle stage ~~and~~is positionable between ~~the~~said projection optic system and ~~the~~said illuminator optic system.

8. (Currently amended) The lithography system of claim 1-7, wherein ~~a~~said reticle table and ~~the~~said reticle stage are removable through ~~the~~said reticle chamber opening in a plane which is substantially perpendicular to a source illuminating from ~~the~~said illuminator optic system.

9. (Currently amended) The lithography system of claim 1-7, further comprising a body structure which is mounted to a lower portion of the reticle chamber, ~~a~~said projection optic system and ~~an~~said illuminator optic system being mounted to ~~the~~said body structure.

10. (Currently amended) The lithography system of claim 1-21, wherein ~~the~~said reticle chamber maintenance panel is semi-cylindrically shaped.

Claim 11 has been cancelled.

12. (Currently amended) The lithography system of claim 1, wherein ~~the~~said reticle chamber opening provides access to substantially a center of gravity of

the-said reticle stage.

13. (Currently amended) A lithography system, comprising:

    a reticle chamber having a reticle chamber angled opening,

    a reticle chamber maintenance panel which is removably mounted to the reticle chamber over the said reticle chamber angled opening;

    an optical system for illuminating and projecting a source;

    a reticle stage having a reticle table, the said reticle table positioned between components of the said optical system and housed with the said reticle stage within the said reticle chamber,

    wherein the said reticle chamber angled opening provides access to the said reticle stage.

14. (Currently amended) The lithography system of claim 13, wherein the said reticle chamber angled opening provides access to the said reticle stage at substantially a center of gravity.

15. (Currently amended) The lithography system of claim 14, wherein the said reticle stage is removable from the said reticle chamber via the said reticle chamber angled opening.

16. (Currently amended) The lithography system of claim 14, wherein the said reticle stage is removable from the said reticle chamber via the said reticle chamber angled opening in a first direction which is in a plane substantially horizontal parallel to the reticle table.

17. (Currently amended) The lithography system of claim 13-18, wherein the said reticle chamber

maintenance panel is pivotably mounted to the reticle chamber.

18. (Currently amended) The lithography system of claim 13-16, wherein the said reticle angled chamber angled opening is at an angle of approximately 45° with relation to the said reticle chamber such that the said reticle chamber maintenance panel is removed, the said reticle stage partially extends from the said reticle chamber.

19. (Currently amended) The lithography system of claim 13-16, further comprising a body structure which is mounted to a lower portion of the said reticle chamber, the said projection optic and the said illuminator optic being mounted to the said body structure during the removal of the said reticle table and the said reticle stage.

20. (Currently amended) The lithography system of claim 13-18, wherein the said reticle chamber maintenance panel is semi-cylindrically shaped.

21. (New) The lithography system of claim 1, further comprising a reticle chamber maintenance panel, wherein said reticle chamber maintenance panel is removably mounted to said reticle chamber over said reticle chamber angled opening.